

EDDY CURRENT DETECTION DEVICE AND POLISHING APPARATUS

ABSTRACT

An eddy current detection device configured to form a stronger magnetic field in a polishing target and a polishing apparatus employing the same eddy current detection device are provided. An eddy current detection device that can be disposed near a semiconductor wafer on which a conductive film is formed includes a plurality of eddy current sensors. The plurality of eddy current sensors are disposed near to one another. Each of the plurality of eddy current sensors includes a pot core, an exciting coil disposed in the pot core and configured to form an eddy current in the conductive film, and a detection coil disposed in the pot core and configured to detect the eddy current formed in the conductive film.

[Selected Drawing] Fig. 6